

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Priority Application Serial No. 09/388,826
Priority Filing Date September 1, 1999
Inventor Weimin Li et al.
Assignee Micron Technology, Inc.
Priority Group Art Unit 2812
Priority Examiner M. Whipple
Attorney's Docket No. MI22-1398
Title: Low k Interlevel Dielectric Layer Fabrication Methods

PRELIMINARY AMENDMENT

To: Assistant Commissioner for Patents
Washington, D.C. 20231

From: Mark S. Matkin (Tel. 509-624-4276; Fax 509-838-3424)
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Sir:

Please enter the following amendments prior to examining the
above-identified application. Applicant amends and remarks as follows:
[unless otherwise indicated, deletions are bracketed, additions are
underlined].

AMENDMENTS

In the Specification

At p. 2, line 15, replace "a exemplary" with --an exemplary--.